



DEPOSITION SYSTEMS FOR COMPOUND SEMICONDUCTORS  
**Close Coupled Showerhead®** 3 x 2 inch · 6 x 2 inch

**AIXTRON**  
Our technology. Your future.

MOCVD systems for R&D and small scale production

# Close Coupled Showerhead® 3 x 2 inch · 6 x 2 inch

## Product Overview

- ▶ Proven Close Coupled Showerhead®
  - True scaling from R&D to mass production
  - Inherently uniform and reproducible growth for all material systems – focus your effort on material and device development
  - High flexibility in process window for excellent material quality and uniformity
- ▶ Ideal for small R&D budgets: lowest running cost
  - Low gas flows and high precursor efficiency
  - Easy and low cost maintenance
- ▶ Available applications
  - GaN, InP, GaAs, InSb, GaInNAs, II-VI, for others please talk to us!
- ▶ Available configurations
  - 3 x 2 inch, 1 x 4 inch, 1 x 3 inch, 1 x 2 inch – by simple carrier exchange
  - 6 x 2 inch, 3 x 3 inch, 1 x 6 inch – by simple carrier exchange
- ▶ Numerous customer references worldwide!

## Features

- ▶ Reliable 3-zone heater
- ▶ High flexibility for optional MO and hydride sources
- ▶ Digital mass flow controllers and pressure controllers
- ▶ Professional AIXACT® Advanced Control System with HTML based GUI
- ▶ Compact foot print

## Optional

- ▶ Dynamic process gap adjustment – effective process tuning for higher performance
- ▶ 1300 °C surface temperature kit
- ▶ Versatile in-situ monitoring portfolio: Laytec EpiTT, EpiCurveTT, many others on request
- ▶ AIXTRON ARGUS thermal mapping device
- ▶ AIXTRON's Epison gas concentration sensors for improved accuracy of precursor injection

## CCS Flip Top Reactor (3 x 2 inch · 6 x 2 inch)



### Typical CCS: true scaling

